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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Sheldon Aronowitz, Valeriy Sukharev, )  
John Haywood, James P. Kimball, )  
Helmut Puchner, Ravindra Manohar )  
Kapre, and Nicholas Eib )

Filed: Herewith )

) Group Art Unit: Unknown

Serial Number: Unknown )

) Examiner: Unknown

Title: "Process for Etching a Controllable Thickness of Oxide )  
on an Integrated Circuit Structure on a Semiconductor )  
Substrate Using Nitrogen Plasma and an RF Bias )  
Applied to the Substrate" )

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.56

Honorable Commissioner of Patents  
and Trademarks  
Washington, D.C. 20231

Date: 12/15/99

Sir:

Pursuant to 37 CFR 1.56, Applicants hereby submit the references listed on the attached form PTO-1449 (modified). Copies of each of the references are enclosed.

Respectfully submitted,

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